Peer Zalm

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Info

After mastering in Mathematical Statistics (1973) and Experimental Physics (1974), I obtained a PhD in Nuclear Physics, all at Utrecht State University.

I joined Philips Research Laboratories in Eindhoven in 1978 to
work on compatibility of future and existing transmission-standards plus ergonomic system aspects of high definition TV.

In 1981 I relocated to the surface science group. where I investigated particle-solid interactions (ion beam deposition and modification of materials, physical and chemical sputtering and ion-induced secondary electron emission), interrupted by a 1½ year study on silicon molecular beam (hetero-)epitaxy at the FOM Institute for Atomic and Molecular Physics in Amsterdam.

After an intermission in 1987/8, co-ordinating high temperature supercon-ductivity research, I was appointed senior scientist in the surface analysis group, leading the dynamic SIMS team. A merger with analysis facilities at the Centre of Manufacturing Technology enabled me to get hands-on experience with XPS, AES, static SIMS. Latest addition: RBS.

Since August 2011 I am retired on a full disability pension..

I was a Visiting Professor in the Atomic Collisions Group of the Physics Department at the University of Salford [UK] from 1991-2011 and I acted as a part-time scientific advisor for surface analysis at the FOM institute forf Plasma Physics in Nieuwegein from 2006 to 2009.

I evaluated numerous project proposal for government bodies in the Netherlands, Belgium, Sweden, the United Kingdom, Australia, Hong Kong and the U. S. A. and regularly review papers for scientific journals. Further, I served on a variety of (inter-)national committees, co-edited proceedings, co-organised conferences etc.

Finally, I (co-)authored well over 100 papers plus 2 book chapters and produced 4 U.S.A. patents.

Specialties: Interaction between radiation (electrons, photons or ions) and matter;
Surface analysis techniques and their application.